

IN THE CLAIMS

Please amend the claims as follows:

1. (Currently Amended): A focus ring assembly, comprising:

a focus ring including a step receiving surface, the focus ring being positioned on a substrate holder and located below a backside surface of a substrate, and an outer radial lip surface positioned radially outward from a peripheral edge of the substrate; and

a secondary focus ring positioned on the step receiving surface of the focus ring, the secondary focus ring including an inner radial edge surface positioned radially outward from the peripheral edge of the substrate,

wherein said focus ring is configured to couple to the substrate holder which is configured to support the substrate exposed to a process in a processing system, and said secondary focus ring is configured to reduce deposition of material from said process on the backside surface of said substrate.

2. (Previously Presented): The focus ring assembly as recited in claim 1, wherein said secondary focus ring comprises a compliant material.

3. (Previously Presented): The focus ring assembly as recited in claim 2, wherein said compliant material comprises at least one of silicone rubber, polyimide, and Teflon.

4. (Previously Presented): The focus ring assembly as recited in claim 1, wherein said secondary focus ring comprises a rigid material.

5. (Previously Presented): The focus ring assembly as recited in claim 4, wherein said rigid material comprises at least one of a ceramic material, silicon, silicon carbide, silicon nitride, silicon dioxide, carbon, sapphire, and alumina.

6. (Previously Presented): The focus ring assembly as recited in claim 1, wherein said secondary focus ring comprises silicon having a resistivity less than or equal to $1\ \Omega\text{-cm}$.

7. (Previously Presented): The focus ring assembly as recited in claim 1, wherein a clearance space is formed between said substrate and said focus ring, and said clearance space exposes at least a portion of said backside surface on said substrate and said secondary focus ring reduces said clearance space.

8. (Previously Presented): The focus ring assembly as recited in claim 7, wherein said secondary focus ring reduces exposure of said backside surface.

9. (Previously Presented): The focus ring assembly as recited in claim 1, wherein a portion of said backside surface on said substrate is exposed and wherein said secondary focus ring reduces said exposure of said backside surface.

10-20. (Canceled).

21. (Currently Amended): The focus ring assembly as recited in claim 1, wherein the ~~inner~~ outer radial ~~edge~~ lip surface of the focus ring is positioned radially outward from the ~~inner~~ an outer radial edge surface of the secondary focus ring.

22. (Currently Amended): The focus ring assembly as recited in claim 1, wherein the ~~inner~~ outer radial ~~edge~~ lip surface of the focus ring is positioned radially outward from and in contact with an outer radial edge surface of the secondary focus ring.

23. (Previously Presented): The focus ring assembly as recited in claim 1, wherein the secondary focus ring has an annular shape and a cross-section of the secondary focus ring has a rectangular shape.

24. (Previously Presented): The focus ring assembly as recited in claim 1, wherein the focus ring has an annular shape and a cross-section of the secondary focus ring has an L-shape.

25. (Previously Presented): The focus ring assembly as recited in claim 1, wherein the secondary focus ring is positioned entirely radially outward from the substrate.

26. (Previously Presented): The focus ring assembly as recited in claim 1, wherein the secondary focus ring includes an upper surface that is substantially planar with a top surface of the substrate.

27. (Previously Presented): The focus ring assembly as recited in claim 26, wherein the focus ring includes an upper surface that is substantially planar with the upper surface of the secondary focus ring and the top surface of the substrate.

28. (New): The focus ring assembly as recited in claim 1, wherein the entire secondary focus ring is positioned radially inside of the outer radial lip surface of the focus ring.

29. (New): The focus ring assembly as recited in claim 1, wherein the focus ring extends further radially inward than the secondary focus ring.

30. (New): A processing apparatus, comprising:
a substrate holder;
a substrate positioned on the substrate holder; and
focus ring assembly coupled to the substrate holder, the focus ring assembly comprising:
a focus ring including a step receiving surface, the focus ring being positioned on the substrate holder and located below a backside surface of the substrate, and an outer radial lip surface positioned radially outward from a peripheral edge of the substrate, and
a secondary focus ring positioned on the step receiving surface of the focus ring, the secondary focus ring including an inner radial edge surface positioned radially outward from the peripheral edge of the substrate such that a clearance space exists between the peripheral edge of the substrate and the inner radial edge surface of the secondary focus ring.

31. (New): The apparatus as recited in claim 30, wherein the substrate is positioned on the substrate holder such that a cantilevered outer portion of the substrate extends radially outward past an outer edge of the substrate holder.